

Metalorganic Vapor Phase Epitaxy of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ alloys

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The $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ chalcopyrite alloy epilayers were successfully grown on GaAs(001) substrates by low-pressure metalorganic vapor phase epitaxy (LP-MOVPE). A good controllability of the Al composition, x , in the epilayer was demonstrated, *i.e.*, the distribution coefficient of Al was unity.

A quadratic dependence of the exciton resonance energies associated with the uppermost valence bands, which were determined by means of photorefectance measurements, on x was confirmed. Spin-orbit splittings of the epilayers were almost comparable to those of bulk alloy single crystals while magnitudes of crystal-field splittings were larger than those of the bulk crystals, and the results were explained in terms of residual tensile biaxial strain in the epilayers.

1. INTRODUCTION

The $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ quaternary alloys have band gap energies ranging from 1.7 to 2.7 eV [1,2], which cover the visible spectral region from red to blue. It has been very difficult [3,4] to grow high-quality CuAlVI_2 compounds due to an existence of chemically active Al in the matrix. However, metalorganic vapor phase epitaxy (MOVPE) has grown high-quality CuAlSe_2 [5,6] and CuAlS_2 [7] epilayers, both of which have exhibited excitonic emissions.

The lattice parameter a of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ is almost constant for all x (0.5612 nm for CuGaSe_2 and 0.5607 nm for CuAlSe_2) [8,9], and is close to that of GaAs being 0.5642 nm. Therefore this alloy system can be utilized as visible light-emitting devices in the form of the heteroepitaxial layers grown on GaAs (001) substrate. However, only limited information has been available for this alloy system such as optical absorption [10], electrical and PL properties [11] before 1993. We have investigated resonance energies of excitons associated with the uppermost valence bands

to the conduction band and PL spectra as a function of Al composition, x , using bulk $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ alloy single crystals grown by the chemical vapor transport (CVT) method [9].

In the present work, heteroepitaxial growth of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ alloy layers was carried out for the first time by LP-MOVPE. The alloy composition of thin layers was determined using an unique method with an electron-probe microanalyzer (EPMA). Structural, electronic, and optical properties were investigated as a function of x .

2. EXPERIMENT

$\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ alloy epilayers were grown using a vertical quartz reactor LP-MOVPE apparatus (BENTEC SCV-2000QR). The source precursors were pentahaptcyclopentadienylcoppertriethylphosphin (CpCuTEP), triisobutylaluminium (TIBAl), normal-tripropylgallium (TPGa), and diethylselenide (DESe).

The growth temperature and reactor pressure were 600 °C and 4×10^4 Pa, respectively. Pd-purified H_2 was used as a carrier gas. The total H_2 flow rate into the

reactor was 3 ℓ /min. and the gas phase VI / III ratio was 200. The growth rate was typically 0.17 μ m/h, and about 0.5 μ m-thick $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ epilayers were grown on GaAs (001) and GaP (001) substrates.

The surface morphology was observed with a Nomarski interference microscope and a scanning electron microscope (SEM). Lattice images were observed with a transmission electron microscope (TEM). Orientation of the epilayer was evaluated by the x-ray diffraction (XRD) measurements with the $\theta - 2\theta$ method using the $\text{CuK } \alpha$ line. The solid composition of Cu, Al, Ga, and Se in the epilayers were estimated by EPMA, according to the measurement condition optimized by Kariya *et al* [12].

Photoluminescence (PL) and photoreflectance (PR) measurements were carried out between 8K to room temperature (300K:RT). For the pump light of the measurements, the 325.0 nm line of a cw He-Cd laser was used for $x \geq 0.63$. Similarly, the 457.9, 488.0, and 514.5 nm lines of a cw Ar^+ laser were used for $0.34 \leq x \leq 0.63$, $0 \leq x \leq 0.34$, and $x=0$, respectively.

3. RESULTS AND DISCUSSION

The Al composition, x , in the alloy layers agrees with $[\text{TIBAl}]/([\text{TIBAl}]+[\text{TPGa}]_{\text{gas}})$, which indicates that the distribution coefficient of Al is unity. The same results have been found for CVT growth of bulk $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ [9] and $\text{CuAl}_x\text{Ga}_{1-x}\text{SSe}$ [13] alloys. These results imply that MOVPE of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ is in the cation diffusion-limited regime and the thermal equilibrium between the growing surface and the lowermost boundary layer is mostly held.

The surface morphology of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ epilayers become rougher with increasing x . For the $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}$ (001), a mirrorlike surface with a cross hatches along the [100] and [010] direction is observed for $x=0$ (CuGaSe_2) [14]. Cross hatches are observed for all x owing to the lattice mismatch ($\Delta a/a \doteq -0.6\%$ at room temperature) and difference of the thermal expansion coefficients between GaAs

and a axis of the alloys [15]. An wavy morphology is seen for $x \geq 0.43$. The appearance of such a worse morphology implies difficulties in growing alloy layers having higher Al content. The morphology of alloy layers grown on GaP (001) is worse than that of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}$ (001) for all x .

According to the XRD pattern of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}$ (001), the diffraction peaks at around 34° and 69° correspond to the (004) and (008) reflection from the epilayer. The XRD results indicate that $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}$ (001) have their c axis normal to the substrate plane.

An example of the cross-sectional TEM micrograph of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}$ (001) [$x=0.5$] is shown in Fig. 1, which is taken with the incident electron beam along the [110] azimuth of the substrate. As is the case with $\text{CuGaSe}_2/\text{GaAs}$ (001) [14] and $\text{CuAlSe}_2/\text{GaAs}$ (001) [4,16], single-domain lattice images without any amorphous phase are recognized.

The exciton energies of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}$ (001) are plotted as a function of x in Fig.2. As is the case with the bulk $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2$ alloy crystals [9], E_A , E_B , and E_C have nonlinear dependence on x . E_A is approximated by the quadratic dependence on x as:

$$E_A = 2.713x + 1.698(1-x) - 0.26x(1-x) \text{ eV.} \quad (1)$$

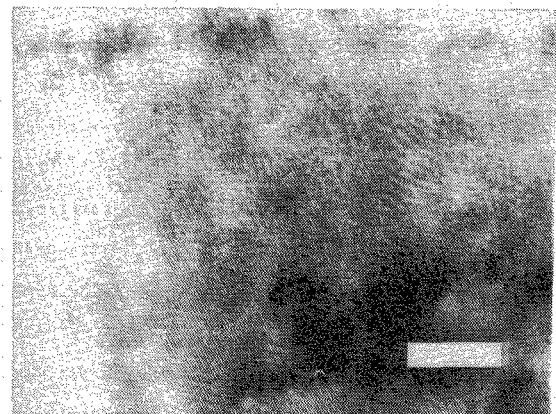


Fig. 1. A cross-sectional TEM micrograph of $\text{CuAl}_{0.5}\text{Ga}_{0.5}\text{Se}_2/\text{GaAs}$ (001) taken with the incidence along the [110] azimuth of the substrate. Marker represents 10 nm.

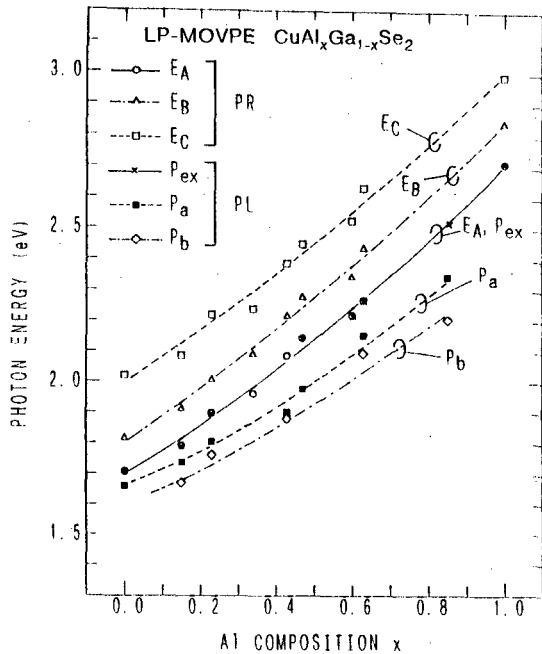


Fig. 2. Exciton energies (E_A , E_B , and E_C) in $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}(001)$ as a function of x at 77 K obtained by the analysis of the PR spectra. PL peak energies (P_{ex} , P_a , and P_b) at 30 K are also plotted.

The constants of the first and second terms are smaller by 17~23meV than those of the bulk alloys[9], as stated above. On the other hand, approximation equations for E_B , and E_C almost agree with those of bulk crystals within the error of $\pm 3\text{meV}$. A bowing parameter obtained from Eq. (1) for E_A is -0.26 eV, the value being comparable with that of the bulk alloy crystals (-0.28 eV) [9].

PL spectra of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}(001)$ measured at 30 K are shown in Fig. 3. Color of the PL changes from red to crimson, orange, yellow, green, and bluish-purple with increasing x from 0 to 1. PL peaks are classified into three types. They are labeled P_{ex} , P_a , and P_b in order from high to low energy, as shown in Fig. 3. It is recognized from Fig.2 that the energy of P_{ex} agrees well with the A exciton energy, indicating that P_{ex} is related to an exciton emission [5,14]. The

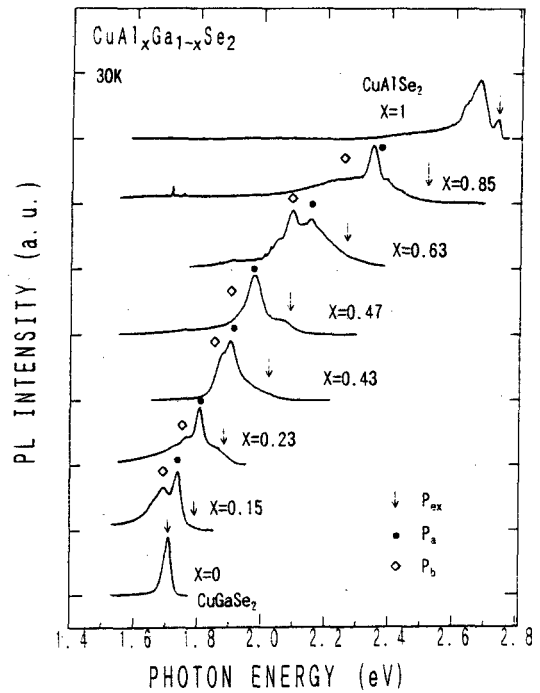


Fig. 3. PL spectra in $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}(001)$ at 30 K. Arrows, closed circles, and open rombs indicate P_{ex} , P_a , and P_b peaks, respectively.

PL peak at 2.680 eV in CuAlSe_2 has been assigned as a bound exciton emission [5,6]. Relative P_{ex} intensity against other PL peak intensities in the PL spectra of alloy layers ($x \neq 0,1$) is weaker than those in the spectra of terminate compounds. This result suggests poor quality of alloy layers, especially for those having higher Al content.

The peak P_a located below P_{ex} dominates the PL spectra of $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}(001)$ ($x \neq 0,1$), as can be seen in Fig. 3. Occasionally, P_a was found in $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}(001)$ at low temperatures [17]. P_a has been assigned to the radiative transition of a free electron with a bound hole (F-B emission) [17]. Excitation intensity dependence of PL peak energy is examined for all x . An absence of the energy shift of P_a indicates that P_a is not a donor-acceptor (D-A) pair emission. Therefore P_a in $\text{CuAl}_x\text{Ga}_{1-x}\text{Se}_2/\text{GaAs}(001)$

is assigned to a F-B transition, similar to the case of CuGaSe₂, because the plots of the P_a peak energy can smoothly be connected with increasing x (data not shown).

4. CONCLUSIONS

CuAl _{x} Ga _{$1-x$} Se₂ alloy epilayers were grown on GaAs (001) by LP-MOVPE. All alloy epilayers had their c axis normal to the substrate plane. A combination of TIBAl and TPGa allowed us to control the alloy composition by adjusting the gas phase input molar fraction; the distribution coefficient of Al was found to be unity.

A quadratic dependence of exciton energies on x was confirmed. Spin-orbit splittings of CuAl _{x} Ga _{$1-x$} Se₂/GaAs (001) were almost the same as those of the bulk alloy crystals while magnitudes of crystal-field splittings were larger than those for the bulk crystals. The increase of the magnitude of $-\Delta_{cf}$ was attributed to the residual tensile biaxial strain in the epilayers.

Color of the low-temperature PL changed from red to bluish-purple with increasing x . A peak due to free-to-acceptor transition dominated the PL spectra of CuAl _{x} Ga _{$1-x$} Se₂/GaAs (001).

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